



Atty. Dkt. 7989/Etch/Silicon/JB

In re Application of:

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**Group Art Unit: 2812**

Examiner:

**For: Method of Controlling Critical Dimension Microloading of Photoresist Trimming Process by Selective Sidewall Polymer Deposition**

**CERTIFICATE OF MAILING**

37 CFR 1.8

8/3/2004  
Date

Signature

## PRELIMINARY AMENDMENT

Amendments to the Specification begin on page 2 of this paper. Amendments to the claims are reflected in the listing which begins on page 5 of this paper. Remarks begin on page 8 of this paper.